

Title (en)

Stiffening layers for the relaxation of strained layers

Title (de)

Versteifungsschichten zur Relaxation von verspannten Schichten

Title (fr)

Couches de durcissement pour le relâchement de couches contraintes

Publication

EP 2159836 A1 20100303 (EN)

Application

EP 08290797 A 20080825

Priority

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Abstract (en)

The present invention relates to a method for relaxing a strained material layer, comprising providing a strained material layer and a low-viscosity layer formed on a first face of the strained material layer; forming a stiffening layer on at least one part of a second face of the strained material layer opposite to the first face thereby forming a multilayer stack; and subjecting the multilayer stack to a heat treatment thereby at least partially relaxing the strained material layer.

IPC 8 full level

H01L 21/84 (2006.01); **H01L 21/20** (2006.01)

CPC (source: EP KR US)

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Citation (search report)

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Designated extension state (EPC)

AL BA MK RS

DOCDB simple family (publication)

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DOCDB simple family (application)

EP 08290797 A 20080825; CN 200980132031 A 20090702; EP 2009004790 W 20090702; JP 2011524209 A 20090702; KR 20117006815 A 20090702; US 200913055123 A 20090702